

Amendments to the Claims

Claims 1-14 (canceled)

Claim 15 (currently amended). A plasma processing system, comprising:

a set of rings, including a top ring and a set of lower rings having at least one lower ring;

a stepped hanger structure coupled to said top ring, said stepped hanger structure supporting said set of lower rings;

a hanger assembly including a plunger shaft and a hanger adapter lip portion, said hanger adapter lip portion being fixed relative to said plunger shaft;

a receiving bore defined by a first cavity in said top ring, wherein a longitudinal axis of said first cavity is substantially parallel to a longitudinal axis of said plunger shaft, and wherein said first cavity is larger than said hanger adapter lip portion; and

a locking bore defined by a second cavity in said top ring, wherein said stepped hanger structure is radially offset from said locking bore, and a longitudinal axis of said second cavity is substantially parallel to said longitudinal axis of said plunger shaft, and wherein said second cavity is smaller than said hanger lip portion, and said receiving bore and said locking bore are connected.

Claim 16 (previously presented). The plasma processing system of claim 15, wherein each of said set of rings is formed of a dielectric material.

Claim 17 (previously presented). The plasma processing system of claim 16, wherein said dielectric material is quartz.

Claim 18 (previously presented). The plasma processing system of claim 15, wherein said hanger adapter is positioned in said locking bore during plasma processing.

Claim 19 (previously presented). The plasma processing system of claim 15, wherein said top ring is secured by moving said set of rings in a direction substantially parallel to said longitudinal axis of said plunger shaft to insert said hanger lip portion into said receiving bore of said top ring, and then rotating said set of rings to seat said hanger lip portion into said locking bore.

Claim 20(canceled)

Claim 21(previously presented). The plasma processing system of claim 15, wherein said stepped hanger structure is coupled only to said top ring of said set of rings.

Claim 22(previously presented). The plasma processing system of claim 21, wherein said hanger lip portion is coupled only to said top ring of said set of rings.

Claim 23(previously presented). The plasma processing system of claim 15, wherein said stepped hanger structure is coupled only to said top ring of said set of rings.

Claim 24(previously presented). The plasma processing system of claim 23, wherein said hanger lip portion is coupled only to said top ring of said set of rings.

Claim 25(previously presented). The plasma processing system of claim 15, wherein said stepped hanger structure further includes a hanger adapter shaft portion configured to attach to said hanger adapter lip portion and said plunger shaft.

Claim 26(previously presented). The plasma processing system of claim 15, wherein said locking bore is counter-sunk in a lower surface of said top ring.

Claim 27 (currently amended). In a plasma processing system, a method of attaching a focus ring assembly comprising:

providing said focus ring assembly, said focus ring assembly including

a set of rings, said set of rings including a top ring and a set of lower rings having at least one lower ring,

a stepped hanger structure coupled to said top ring, said stepped hanger structure supporting said set of lower rings,

a hanger assembly including a plunger shaft and a hanger adapter lip portion, said hanger adapter lip portion being fixed relative to said plunger shaft,

a receiving bore defined by a first cavity in said top ring, wherein a longitudinal axis of said first cavity is substantially parallel to a longitudinal axis of said plunger shaft, and wherein said first cavity is larger than said hanger adapter lip portion, and

a locking bore defined by a second cavity in said top ring, wherein stepped hanger structure is radially offset from said locking bore, and a longitudinal axis of said second cavity is substantially parallel to said longitudinal axis of said plunger shaft, and wherein said second cavity is smaller than said hanger lip portion, and said receiving bore and said locking bore are connected; and

moving said set of rings in a direction substantially parallel to a longitudinal axis of said plunger shaft to insert said hanger lip portion into said receiving bore of said top ring, and then rotating said set of rings to seat said hanger lip portion into said locking bore.

Claim 28 (previously presented). The method of claim 27, wherein each of said set of rings is formed of a dielectric material.

Claim 29 (previously presented). The method of claim 28, wherein said set dielectric material is quartz.

Claim 30 (previously presented). The method of claim 27, wherein said hanger adapter is positioned in said locking bore during plasma processing.

Claim 31 (canceled)

Claim 32 (previously presented). The method of claim 27, wherein said stepped hanger structure is coupled only to said top ring of said set of rings.

Claim 33(previously presented). The method of claim 32, wherein said hanger lip portion is coupled only to said top ring of said set of rings.

Claim 34(previously presented). The method of claim 27, wherein said stepped hanger structure is coupled only to said top ring of said set of rings.

Claim 35(previously presented). The method of claim 34, wherein said hanger lip portion is coupled only to said top ring of said set of rings.

Claim 36(previously presented). The method of claim 27, wherein said locking bore is counter-sunk in a lower surface of said top ring.